

## MScs

- **George Kokkoris**  
*Simulation of SiO<sub>2</sub> and Si features in fluorocarbon plasmas (1999)*
- **George Kordogiannis**  
*Dry etching of polymeric materials using lithography in high density inductively coupled plasma reactor (2000)*
- **Alexandros Koulides**  
*Computational methods for plasma etching of contact holes of integrated circuits (2001)*
- **Konstantinos Boukouras**  
*Etching of silicon surfaces in high density plasma reactor and study of surface and line edge roughness (2003)*
- **Olga Brani**  
*Study of silicon and silicon containing polymer surfaces after plasma treatment (2004)*
- **Evrymahos Matrozos**  
*Selective deposition of fluorocarbon films and application in protein arrays (2005)*
- **Panagiotis Papassimakis**  
*Fabrication and simulation of microstructures by plasma processing (2005)*
- **Katerina Tsougeni**  
*Modification of PDMS surfaces in O<sub>2</sub>-based plasmas (2005)*
- **Paraskevi Geka**  
*Modeling of the gas phase of oxygen plasma discharges with global zero dimensional models (2006)*
- **Eleni Zakka**  
*Plasma etching of composite materials: Stochastic simulation of roughness formation (2006)*
- **Paraskevi Xydi**  
*Simulation of etching using the narrow band level set method (2006)*
- **Panagiotis Angelikopoulos**  
*Monte-Carlo roughening during thin film plasma etching (2006)*